L26 ANSWER 39 OF 40 CAPLUS COPYRIGHT 2003 ACS on STN
AN 2002:314503 CAPLUS
DN 136:348304
TI Positive photosensitive composition
IN Kodama, Kunihiko; Aoai, Toshiaki
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 148 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1199603	A1	20020424	EP 2001-124329	20011019
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
	JP 2002131897	A2	20020509	JP 2000-321128	20001020
	JP 2002214774	A2	20020731	JP 2001-132546	20010427
	US 2002102491	A1	20020801	US 2001-978103	20011017
PRAI	JP 2000-321128	A	20001020		
	JP 2000-352899	A	20001120		
	JP 2001-132546	A	20010427		

AB A pos. photosensitive compn. comprises a compd. capable of generating a specified sulfonic acid upon irradn. with one of an actinic ray and radiation and a resin capable of decompg. under the action of an acid to increase the soly. in an alkali developer.

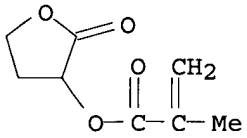
IT **195000-67-0 216308-45-1 250378-10-0**
258879-87-7 288303-55-9 297156-40-2
301664-71-1 304441-22-3 324770-96-9
357413-69-5 398141-19-0 414911-37-8
414911-60-7 414911-65-2 414911-75-4
414911-76-5 415920-54-6
RL: TEM (Technical or engineered material use); USES (Uses)
(photo-acid generator used in pos. **photoresist** compn.)

RN 195000-67-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

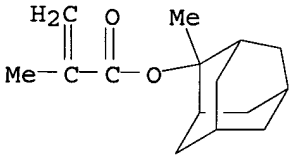
CRN 195000-66-9
CMF C8 H10 O4



230 - 232

CM 2

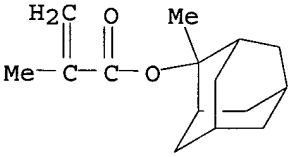
CRN 177080-67-0
CMF C15 H22 O2



RN 216308-45-1 CAPLUS
CN 2-Propenoic acid, 2-methyl-, polymer with 2-methyltricyclo[3.3.1.13,7]dec-2-yl 2-methyl-2-propenoate and tetrahydro-4-methyl-2-oxo-2H-pyran-4-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 177080-67-0
CMF C15 H22 O2



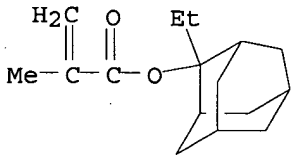
CM 2

CRN 177080-66-9
CMF C10 H14 O4

RN 250378-10-0 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-ethyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

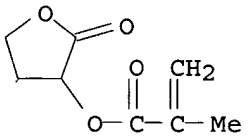
CM 1

CRN 209982-56-9
CMF C16 H24 O2



CM 2

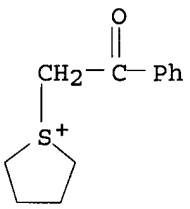
CRN 195000-66-9
CMF C8 H10 O4



RN 301664-71-1 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

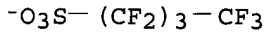
CM 1

CRN 58162-29-1
CMF C12 H15 O S



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S



L26 ANSWER 40 OF 40 CAPLUS COPYRIGHT 2003 ACS on STN
AN 2002:119352 CAPLUS
DN 136:175472
TI Positive photosensitive composition for photofabrication using deep UV ray
IN Kodama, Kunihiko; Aoai, Toshiaki
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 120 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI EP 1179750	A1	20020213	EP 2001-117796	20010802
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2002122994	A2	20020426	JP 2001-188670	20010621
US 2002051933	A1	20020502	US 2001-921691	20010806
US 6492091	B2	20021210		
PRAI JP 2000-240059	A	20000808		

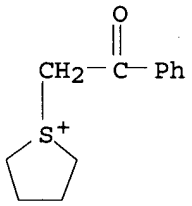
AB A pos. photosensitive compn. comprises: (A) a compd. generating an acid upon irradn. with one of an actinic ray and radiation; (B) a resin contg. a monocyclic or polycyclic alicyclic hydrocarbon structure and increasing the soly. to an alkali developer by the action of an acid; and (C) an onium salt of carboxylic acid. The present invention relates to a pos. photosensitive compn. for use in the prodn. process of a semiconductor such as IC, in the prodn. of a circuit board such as liq. crystal and thermal head, and in other photofabrication processes.

IT **398141-62-3 398141-63-4**
RL: TEM (Technical or engineered material use); USES (Uses)
(onium salt; deep UV photofabrication pos. **photoresist** compn. contg.)

RN 398141-62-3 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, methanesulfonate (9CI) (CA INDEX NAME)

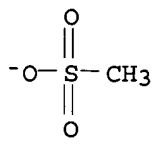
CM 1

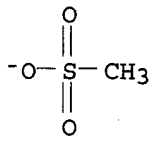
CRN 58162-29-1
CMF C12 H15 O S



CM 2

CRN 16053-58-0
CMF C H3 O3 S

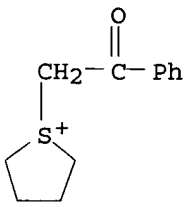




RN 398141-63-4 CAPLUS
CN Cholan-24-oic acid, 3,7,12-trihydroxy-, ion(1-), (3.alpha.,5.beta.,7.alpha.,12.alpha.)-, tetrahydro-1-(2-oxo-2-phenylethyl)thiophenium (9CI) (CA INDEX NAME)

CM 1

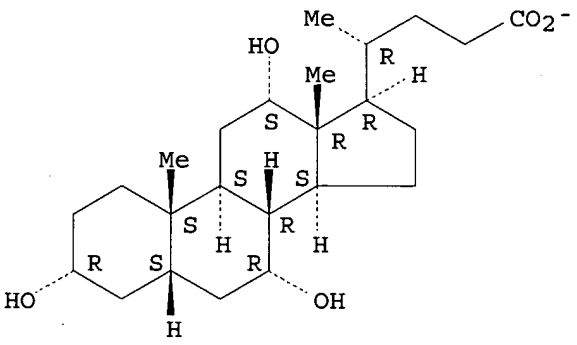
CRN 58162-29-1
CMF C12 H15 O S



CM 2

CRN 298-43-1
CMF C24 H39 O5

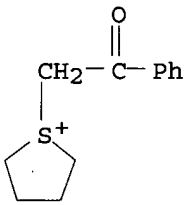
Absolute stereochemistry.



IT **301664-71-1 301664-72-2 398141-19-0 398141-23-6**
RL: TEM (Technical or engineered material use); USES (Uses)
(photoacid generator; deep UV photofabrication pos. **photoresist** compn. contg.)
RN 301664-71-1 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1
CMF C12 H15 O S



CM 2

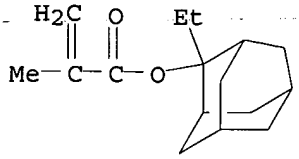
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 301664-72-2 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with 1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoro-1-octanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

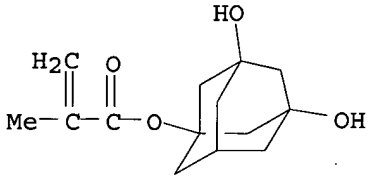
CM 2

CRN 209982-56-9
CMF C16 H24 O2



CM 3

CRN 115522-15-1
CMF C14 H20 O4



L29 ANSWER 36 OF 37 CAPLUS COPYRIGHT 2003 ACS on STN
AN 2002:314503 CAPLUS
DN 136:348304
TI Positive photosensitive composition
IN Kodama, Kunihiko; Aoai, Toshiaki
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 148 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1199603	A1	20020424	EP 2001-124329	20011019
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
	JP 2002131897	A2	20020509	JP 2000-321128	20001020
	JP 2002214774	A2	20020731	JP 2001-132546	20010427
	US 2002102491	A1	20020801	US 2001-978103	20011017
PRAI	JP 2000-321128	A	20001020		
	JP 2000-352899	A	20001120		
	JP 2001-132546	A	20010427		

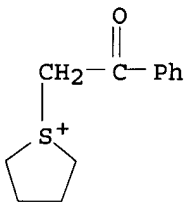
AB A pos. photosensitive compn. comprises a compd. capable of generating a specified sulfonic acid upon irradn. with one of an actinic ray and radiation and a resin capable of decompg. under the action of an acid to increase the soly. in an alkali developer.

IT **301664-71-1 398141-19-0 414911-37-8**
414911-60-7 414911-65-2 414911-75-4
414911-76-5 414911-87-8 414911-88-9
RL: TEM (Technical or engineered material use); USES (Uses)
(photo-acid generator used in pos. **photoresist** compn.)

RN 301664-71-1 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

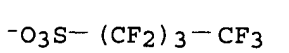
CM 1

CRN 58162-29-1
CMF C12 H15 O S



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S

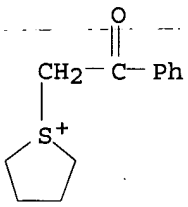


RN 398141-19-0 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with

trifluoromethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

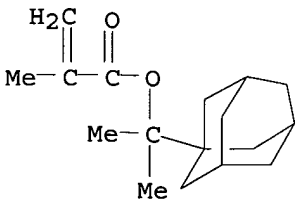
CRN 58162-29-1
CMF C12 H15 O S



RN 414911-87-8 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 1-methyl-1-tricyclo[3.3.1.13,7]dec-1-ylethyl ester, polymer with 3-hydroxytricyclo[3.3.1.13,7]dec-1-yl 2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

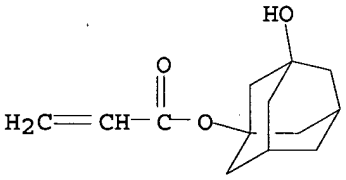
CM 1

CRN 279218-76-7
CMF C17 H26 O2



CM 2

CRN 216581-76-9
CMF C13 H18 O3



CM 3

CRN 195000-66-9
CMF C8 H10 O4

```
     (FILE 'HOME' ENTERED AT 16:30:39 ON 20 AUG 2003)

     FILE 'REGISTRY' ENTERED AT 16:30:57 ON 20 AUG 2003
L1                SCREEN 970 AND 2067
L2                STRUCTURE UPLOADED
L3                QUE L2 AND L1
L4                SCREEN 970 AND 2067
L5                STRUCTURE UPLOADED
L6                QUE L5 AND L4
L7                SCREEN 970 AND 2067
L8                STRUCTURE UPLOADED
L9                QUE L8 AND L7
L10               SCREEN 963 AND 970 AND 1006 AND 2067
L11               STRUCTURE UPLOADED
L12               QUE L11 AND L10
L13               SCREEN 970 AND 2067
L14               STRUCTURE UPLOADED
L15               QUE L14 AND L13
L16               SCREEN 970 AND 2067
L17               STRUCTURE UPLOADED
L18               QUE L17 AND L16
L19           922 S L3 FULL

     FILE 'CAPLUS' ENTERED AT 16:33:56 ON 20 AUG 2003
L20           452 S L19
L21         32183 S PHOTORESIST OR RESIST COMPOSITION
L22           391 S L20 AND L21

     FILE 'REGISTRY' ENTERED AT 16:36:46 ON 20 AUG 2003
L23               STRUCTURE UPLOADED
L24           130 S L23 FULL

     FILE 'CAPLUS' ENTERED AT 16:37:07 ON 20 AUG 2003
L25           127 S L24
L26            40 S L22 AND L25

     FILE 'REGISTRY' ENTERED AT 16:46:33 ON 20 AUG 2003
L27           439 S L18 FULL

     FILE 'CAPLUS' ENTERED AT 16:47:03 ON 20 AUG 2003
L28           139 S L27
L29            37 S L21 AND L28 AND L25

     FILE 'REGISTRY' ENTERED AT 16:53:14 ON 20 AUG 2003

=> s l15 full
FULL SEARCH INITIATED 16:53:26 FILE 'REGISTRY'
FULL SCREEN SEARCH COMPLETED -    581 TO ITERATE

100.0% PROCESSED     581 ITERATIONS                          439 ANSWERS
SEARCH TIME: 00.00.01

L30           439 SEA SSS FUL L14 AND L13

=>
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L29 ANSWER 37 OF 37 CAPLUS COPYRIGHT 2003 ACS on STN
AN 2002:119352 CAPLUS
DN 136:175472
TI Positive photosensitive composition for photofabrication using deep UV ray
IN Kodama, Kunihiko; Aoai, Toshiaki
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 120 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1179750	A1	20020213	EP 2001-117796	20010802
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	JP 2002122994	A2	20020426	JP 2001-188670	20010621
	US 2002051933	A1	20020502	US 2001-921691	20010806
	US 6492091	B2	20021210		
PRAI	JP 2000-240059	A	20000808		

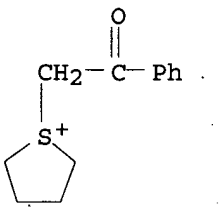
AB A pos. photosensitive compn. comprises: (A) a compd. generating an acid upon irradn. with one of an actinic ray and radiation; (B) a resin contg. a monocyclic or polycyclic alicyclic hydrocarbon structure and increasing the soly. to an alkali developer by the action of an acid; and (C) an onium salt of carboxylic acid. The present invention relates to a pos. photosensitive compn. for use in the prodn. process of a semiconductor such as IC, in the prodn. of a circuit board such as liq. crystal and thermal head, and in other photofabrication processes.

IT **398141-62-3 398141-63-4**
RL: TEM (Technical or engineered material use); USES (Uses)
(onium salt; deep UV photofabrication pos. **photoresist** compn. contg.)

RN 398141-62-3 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, methanesulfonate (9CI) (CA INDEX NAME)

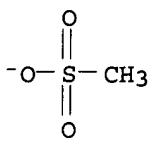
CM 1

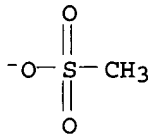
CRN 58162-29-1
CMF C12 H15 O S



CM 2

CRN 16053-58-0
CMF C H3 O3 S

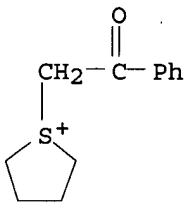




RN 398141-63-4 CAPLUS
CN Cholan-24-oic acid, 3,7,12-trihydroxy-, ion(1-), (3.alpha.,5.beta.,7.alpha.,12.alpha.)-, tetrahydro-1-(2-oxo-2-phenylethyl)thiophenium (9CI) (CA INDEX NAME)

CM 1

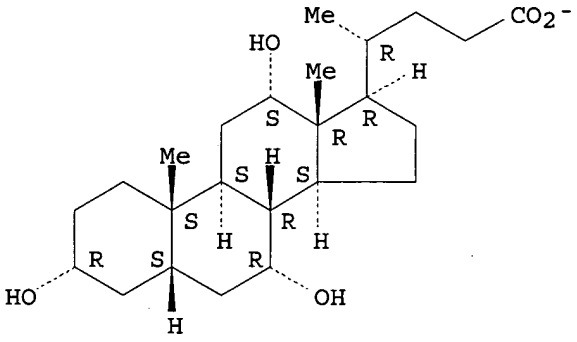
CRN 58162-29-1
CMF C12 H15 O S



CM 2

CRN 298-43-1
CMF C24 H39 O5

Absolute stereochemistry.



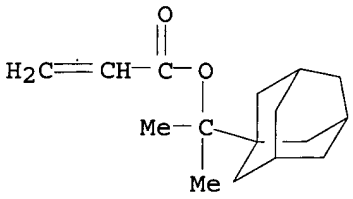
IT **301664-71-1 301664-72-2 398141-19-0**
398141-23-6
RL: TEM (Technical or engineered material use); USES (Uses)
(photoacid generator; deep UV photofabrication pos. **photoresist** compn. contg.)

391613-77-7 CAPLUS

CN 2-Propenoic acid, 3-hydroxytricyclo[3.3.1.13,7]dec-1-yl ester, polymer with .alpha.,.alpha.-dimethylbicyclo[2.2.1]hept-5-ene-2-methanol, 2,5-furandione and 1-methyl-1-tricyclo[3.3.1.13,7]dec-1-ylethyl 2-propenoate (9CI) (CA INDEX NAME)

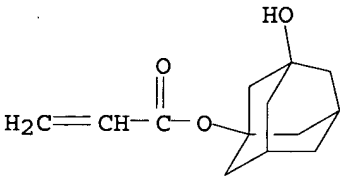
CM 1

CRN 300833-10-7
CMF C16 H24 O2



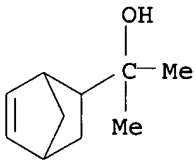
CM 2

CRN 216581-76-9
CMF C13 H18 O3



CM 3

CRN 22497-08-1
CMF C10 H16 O



L5 ANSWER 3 OF 30 CAPLUS COPYRIGHT 2002 ACS
AN 2002:793943 CAPLUS
DN 137:317924
TI Perfluoroalkylsulfonic acid compounds for photoresists
IN Ferreira, Lawrence; Blakeney, Andrew J.; Spaziano, Gregory Dominic; Dimov, Ognian; Kocab, Thomas J.; Hatfield, John P.
PA Arch Specialty Chemicals, Inc., USA
SO PCT Int. Appl., 81 pp.
CODEN: PIXXD2
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2002082185	A1	20021017	WO 2002-US10800	20020405
	W: JP, KR, SG				
	RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR				
PRAI	US 2001-281652P	P	20010405		

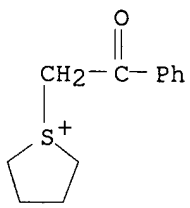
OS MARPAT 137:317924
AB The present invention relates to a photoacid compd. that produce a fluorinated alkyl sulfonic acid having a short perfluoroalkyl chain attached to an ether linkage. The invention photoacid has general structure: R-O(CF2)nSO3X (n = 1-4; R = C1-C12 alkyl or alkenyl, araalkyl, aryl, bicycloalkyl, tricycloalkyl, H, alkyl sulfonic acid, perfluoroalkyl, general structure F((CF2)pO)m(CF2)q-; p = 1-4; m = 0-3; q = 1-4; etc.; X = org. cations and covalently bonded org. radicals). The present invention relates **photoresist** compn comprising such photoacid generator compd.
IT **414911-37-8**
RL: TEM (Technical or engineered material use); USES (Uses)
(photoacid for photoresists compn. and photolithog.)
RN 414911-37-8 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with 1,1,2,2-tetrafluoro-2-(pentafluoroethoxy)ethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

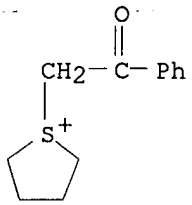
CRN 220689-13-4
CMF C4 F9 O4 S

CM 2

CRN 58162-29-1
CMF C12 H15 O S



IT **58162-29-1**
RL: TEM (Technical or engineered material use); USES (Uses)
(sulfonium cation; prepn. of photoacid for photoresists compn. and photolithog.)
RN 58162-29-1 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)- (9CI) (CA INDEX NAME)



RE.CNT 7 THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L5 ANSWER 10 OF 30 CAPLUS COPYRIGHT 2002 ACS
AN 2002:707243 CAPLUS
DN 137:217798
TI Highly UV-sensitive radically polymerizable compositions without sensitizers
IN Uesugi, Takahiko; Arishima, Shinji; Yagi, Tamao
PA Toyo Ink Mfg. Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 23 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

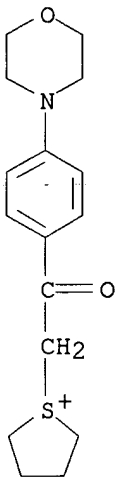
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002265512	A2	20020918	JP 2001-67938	20010312
	WO 2002072640	A1	20020919	WO 2002-JP2303	20020312

W: CN, KR, US
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR

PRAI JP 2001-67938 A 20010312
OS MARPAT 137:217798
AB The compns., useful for moldings, coatings, photoresists, etc., contain initiators C6R5COCR3R4S+R1R2.Z- (R = H, alkyl, alkoxy, acyloxy, halo, NR5R6, .gtoreq.1 of R are NR5R6, R1-R6 = H, alkyl, aryl; Z- = anion) and radically polymerizable compds. Thus, a cyclohexanone soln. of 100 parts pentaerythritol triacrylate and 6 parts p-Me2NC6H4COCH2S+Me2.BBuPh- manufd. from p-Me2NC6H4COCH2S+Me2.Br- and Li+BBuPh- was applied on a glass plate and dried to give a light yellow layer, which was irradiated with UV at 350-380 nm and 80 mJ/cm2 to give a colorless layer.
IT **457645-65-7P**
RL: CAT (Catalyst use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(initiators for highly UV-sensitive radically polymerizable compns. without sensitizers)
RN 457645-65-7 CAPLUS
CN Thiophenium, tetrahydro-1-[2-[4-(4-morpholinyl)phenyl]-2-oxoethyl]-, (T-4)-butyltriphenylborate(1-) (9CI) (CA INDEX NAME)

CM 1

CRN 457645-64-6
CMF C16 H22 N O2 S


O
N
C
O
CH2
S+

L5 ANSWER 16 OF 30 CAPLUS COPYRIGHT 2002 ACS
AN 2002:314503 CAPLUS
DN 136:348304
TI Positive photosensitive composition
IN Kodama, Kunihiko; Aoai, Toshiaki
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 148 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1199603	A1	20020424	EP 2001-124329	20011019
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
	JP 2002131897	A2	20020509	JP 2000-321128	20001020
	JP 2002214774	A2	20020731	JP 2001-132546	20010427
	US 2002102491	A1	20020801	US 2001-978103	20011017
PRAI	JP 2000-321128	A	20001020		
	JP 2000-352899	A	20001120		
	JP 2001-132546	A	20010427		

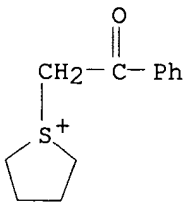
AB A pos. photosensitive compn. comprises a compd. capable of generating a specified sulfonic acid upon irradn. with one of an actinic ray and radiation and a resin capable of decompg. under the action of an acid to increase the soly. in an alkali developer.

IT **301664-71-1 398141-19-0 414911-37-8**
414911-60-7 414911-65-2 414911-75-4
414911-76-5
RL: TEM (Technical or engineered material use); USES (Uses)
(photo-acid generator used in pos. **photoresist** compn.)

RN 301664-71-1 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1
CMF C12 H15 O S



CM 2

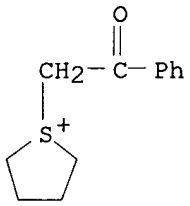
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 398141-19-0 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with trifluoromethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1
CMF C12 H15 O S



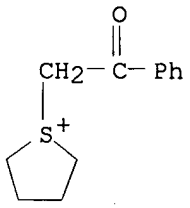
L5 ANSWER 18 OF 30 CAPLUS COPYRIGHT 2002 ACS
AN 2000:739615 CAPLUS
DN 133:315619
TI Positive-working **resist composition**
IN Fujimura, Satoshi; Katashima, Miwa; Haneda, Hideo; Iwai, Takeshi
PA Tokyo Ohka Kogyo Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000292917	A2	20001020	JP 1999-98796	19990406

OS MARPAT 133:315619
AB In the title resist compn. contg. (1) a polymer in which the H atoms of the carboxyl groups are substituted by an acid-dissocg. group having alkali dissoln.-inhibiting ability and the acid-dissocg. group is dissocd. by the action of the acid generated by exposure to increase the soly. to aq. alkali solns. and (2) a compd. generating an acid by irradn. with radiation, the acid generator is a mixt. of (a) a triphenylsulfonium salt having substituted or unsubstituted benzene nuclei and (b) a sulfonium salt I (Ar = aryl; X- = C1-15 fluoroalkylsulfonic acid ion) in a (a)/(b) ratio of 5-25 wt.%. The compn. shows high photosensitivity and provides high resoln. patterns with good profile by using ArF excimer lasers.
IT **301664-71-1 301664-72-2**
RL: TEM (Technical or engineered material use); USES (Uses)
(pos. resist compn. contg. polymer having acid decomposable group and sulfonium compds. acid generators)
RN 301664-71-1 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1
CMF C12 H15 O S



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S

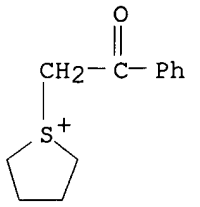
$^{-}O_3S-(CF_2)_3-CF_3$

RN 301664-72-2 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with

1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoro-1-octanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

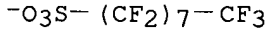
CM 1

CRN 58162-29-1
CMF C12 H15 O S



CM 2

CRN 45298-90-6
CMF C8 F17 O3 S



L5 ANSWER 22 OF 30 CAPLUS COPYRIGHT 2002 ACS
AN 1997:467621 CAPLUS
DN 127:109943
TI Light-sensitive polycyanurate compositions as photoresists and their preparation
IN Hedrick, Jeffrey Curtis; Papathomas, Konstantinos I.; Tisdale, Stephen L.; Viehbeck, Alfred; Gelorme, Jeffrey Donald; Markovich, Voya Rista; Lewis, Thomas H.; Furniss, Stephen Joseph
PA International Business Machines Corporation, USA
SO Jpn. Kokai Tokkyo Koho, 16 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09137059	A2	19970527	JP 1996-242987	19960913
	JP 3177173	B2	20010618		
	US 5919596	A	19990706	US 1997-798592	19970211
PRAI	US 1995-528291	A	19950914		

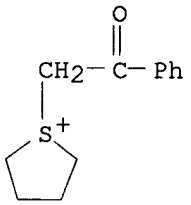
AB The curable crack-resistant compns., useful for circuit boards and electronic packaging, contain (1) thermosetting materials comprising cyanate resins and/or their prepolymers, (2) reactive halogen-contg. thermoplastic resins as modifiers, and (3) photosensitizers. Preferably, component 2 is a F-contg. polyoxyarylene and component 3 contains a cation of a Group IV-VIII transition metal.

IT **58162-30-4 71967-58-3 191981-90-5**
RL: CAT (Catalyst use); USES (Uses)
(photosensitizers; light-sensitive polycyanurate compns. as photoresists)

RN 58162-30-4 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

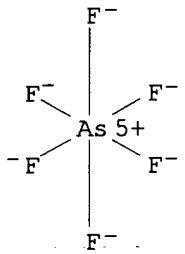
CM 1

CRN 58162-29-1
CMF C12 H15 O S



CM 2

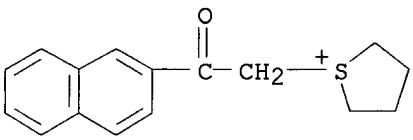
CRN 16973-45-8
CMF As F6
CCI CCS



RN 71967-58-3 CAPLUS
CN Thiophenium, tetrahydro-1-[2-(2-naphthalenyl)-2-oxoethyl]-, tetrafluoroborate(1-) (9CI) (CA INDEX NAME)

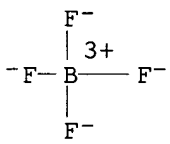
CM 1

CRN 71967-57-2
CMF C16 H17 O S



CM 2

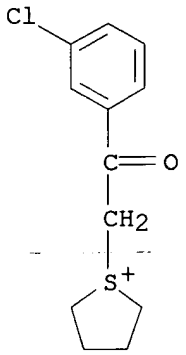
CRN 14874-70-5
CMF B F4
CCI CCS



RN 191981-90-5 CAPLUS
CN Thiophenium, 1-[2-(3-chlorophenyl)-2-oxoethyl]tetrahydro-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

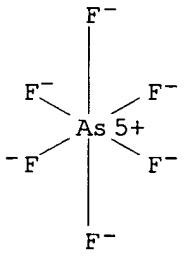
CM 1

CRN 137309-31-0
CMF C12 H14 Cl O S



CM 2

CRN 16973-45-8
CMF As F6
CCI CCS



L5 ANSWER 23 OF 30 CAPLUS COPYRIGHT 2002 ACS
AN 1997:9 CAPLUS
DN 126:39711
TI Visible-light polymerization initiator and visible-light polymerizable composition
IN Kazama, Hideki; Satoh, Takeshi; Oguri, Makoto
PA Tokuyama Corporation, Japan
SO Eur. Pat. Appl., 39 pp.
CODEN: EPXXDW
DT Patent
LA English

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     (FILE 'HOME' ENTERED AT 15:06:55 ON 03 DEC 2002)

     FILE 'REGISTRY' ENTERED AT 15:07:06 ON 03 DEC 2002
L1                STRUCTURE UPLOADED
L2            106 S L1 FULL

     FILE 'CAPLUS' ENTERED AT 15:09:36 ON 03 DEC 2002
L3             96 S L2
L4          30380 S PHOTORESIST OR RESIST COMPOSITION
L5             30 S L3 AND L4

=> d l2
```
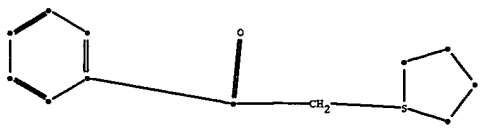

C:\STNEXP4\QUERIES\98800[redacted]str



chain nodes :
6 7 14
ring nodes :
1 2 3 4 5 8 9 10 11 12 13
chain bonds :
3-6 6-14 7-14 13-14
ring bonds :
1-2 1-5 2-3 3-4 4-5 8-9 8-13 9-10 10-11 11-12 12-13
exact/norm bonds :
7-14
exact bonds :
1-2 1-5 2-3 3-4 3-6 4-5 6-14 13-14
normalized bonds :
8-9 8-13 9-10 10-11 11-12 12-13

Match level :
1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:CLASS 7:CLASS 8:Atom 9:Atom
10:Atom 11:Atom 12:Atom 13:Atom 14:CLASS

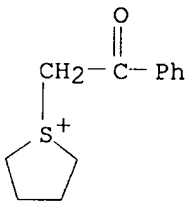
L5 ANSWER 18 OF 30 CAPLUS COPYRIGHT 2002 ACS
AN 2000:739615 CAPLUS
DN 133:315619
TI Positive-working **resist composition**
IN Fujimura, Satoshi; Katashima, Miwa; Haneda, Hideo; Iwai, Takeshi
PA Tokyo Ohka Kogyo Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000292917	A2	20001020	JP 1999-98796	19990406

OS MARPAT 133:315619
AB In the title resist compn. contg. (1) a polymer in which the H atoms of the carboxyl groups are substituted by an acid-dissocg. group having alkali dissoln.-inhibiting ability and the acid-dissocg. group is dissocd. by the action of the acid generated by exposure to increase the soly. to aq. alkali solns. and (2) a compd. generating an acid by irradn. with radiation, the acid generator is a mixt. of (a) a triphenylsulfonium salt having substituted or unsubstituted benzene nuclei and (b) a sulfonium salt I (Ar = aryl; X- = C1-15 fluoroalkylsulfonic acid ion) in a (a)/(b) ratio of 5-25 wt.%. The compn. shows high photosensitivity and provides high resoln. patterns with good profile by using ArF excimer lasers.
IT **301664-71-1 301664-72-2**
RL: TEM (Technical or engineered material use); USES (Uses)
(pos. resist compn. contg. polymer having acid decomposable group and sulfonium compds. acid generators)
RN 301664-71-1 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

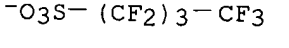
CM 1

CRN 58162-29-1
CMF C12 H15 O S



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S

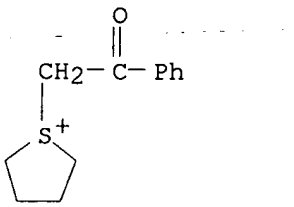


RN 301664-72-2 CAPLUS
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with

1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoro-1-octanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1
CMF C12 H15 O S



CM 2

CRN 45298-90-6
CMF C8 F17 O3 S

$^{-}O_3S-(CF_2)_7-CF_3$